

Form PTO-1449 U.S. DEPARTMENT OF COMMERCE (REV. 8-83) PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO. BU9-99-197		SERIAL NO.	
INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				APPLICANT Furukawa, et al.			
				FILING DATE		GROUP	
U. S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLAS S	SUB- CLASS	FILING DATE IF APPROPRIATE
11/6		5,783,036	07/1998	Shoji	156	643.1	
11/6		5,750,442	05/1998	Jeungling	438	761	
11/6		5,445,710	08/1995	Hori, et al.	156	643.1	
11/6		5,413,966	05/1995	Schoenborn	431	225	
11/6		5,354,417	10/1994	Cheung, et al.	156	643	
11/6		3,830,686	08/1974	Lehrer	95	1R	
FOREIGN PATENT DOCUMENTS							
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLAS S	SUB- CLASS	TRANSLATION YES NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
11/6		Wayne M. Moreau, "Semiconductor Lithography Principles, Practices, and Materials", Microdevices Physics and Fabrication Technologies, 1988, pp. 731-732 and 769-770.					
EXAMINER <i>Kurt Eaton</i>				DATE CONSIDERED <i>3/21/01</i>			
*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							